# Repeater Insertion in *RLC* Lines for Minimum Propagation Delay

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Abstract - A closed form expression for the propagation delay of a CMOS gate driving a distributed RLC line is introduced that is within 5% of dynamic circuit simulations for a wide range of RLC loads. It is shown that the traditional quadratic dependence of the propagation delay on the length of an RC line approaches a linear dependence as inductance effects increase. The closed form delay model is applied to the problem of repeater insertion in RLC interconnect. Closed form solutions are presented for inserting repeaters into RLC lines that are highly accurate with respect to numerical solutions. An RC model as compared to an RLC model creates errors of up to 30% in the total propagation delay of a repeater system. Considering inductance in repeater insertion is also shown to significantly save repeater area and power consumption. The error between the RC and RLC models increases as the gate parasitic impedances decrease which is consistent with technology scaling trends. Thus, the importance of inductance in high performance VLSI design methodologies will increase as technologies scale.

#### I. Introduction

It has become well accepted that interconnect delay dominates gate delay in current deep submicrometer VLSI circuits [1]-[5]. Currently, inductance is becoming more important with faster onchip rise times and longer wire lengths. Wide wires are frequently encountered in clock distribution networks and in upper metal layers. These wires are low resistance wires that can exhibit significant inductive effects. Furthermore, increasing performance requirements are pushing the introduction of new materials for low resistance interconnect [6]. With these trends it is becoming more important to include inductance when modeling on-chip interconnect. Criteria to determine which nets should consider on-chip inductance have been described in [7] and [8].

The focus of this paper is to provide an accurate estimation of the propagation delay of a CMOS gate driving a distributed RLC line as well as to develop design expressions for optimum repeater insertion to minimize the delay of a signal propagating along a distributed RLC line. The paper is organized as follows. In section II, a simple yet accurate propagation delay formula describing a CMOS gate driving a distributed RLC load is presented. In section III, the propagation delay formula is used to develop design expressions for optimum repeater insertion to minimize the propagation delay of a distributed RLC line. Some conclusions are offered in section IV. A mathematical proof of the expressions for optimum repeater insertion in an *RLC* line is provided in the appendix.

## II. Propagation Delay of a CMOS Gate Driving an **RLC** Load

An arbitrary CMOS gate driving an RLC transmission line representation of an interconnect line is shown in Fig. 1.  $R_p$ ,  $L_p$  and  $C_t$  are the total resistance, inductance, and capacitance of the line,

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respectively. The parasitic impedances  $R_t$ ,  $L_t$ , and  $C_t$  are given by  $R_t$ = Rl,  $L_t$  = Ll, and  $C_t$  = Cl, respectively, where R, L, and C are the resistance, inductance, and capacitance per unit length of the interconnect and l is the length of the line.  $R_{tr}$  is the equivalent output resistance of the gate driving the interconnect.  $C_L$  is the input capacitance of the following gate at the end of the interconnect section. A minimum size buffer has an output resistance  $R_0$  and an input capacitance  $C_0$ . The input voltage  $V_{in}$  is a fast rising signal that can be approximated by a step signal.  $V_{out}$  is the far output voltage at the end of the interconnect section.

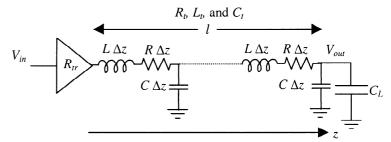


Fig. 1. A CMOS gate driving an RLC transmission line.

From the basic principles of a transmission line [12], the voltage transfer function  $V_{out}(S)/V_{in}(S)$  at the end of a lossy transmission line with a source resistance  $z_s$  and a load impedance  $z_L$  is given by

$$\frac{V_{out}(S)}{V_{in}(S)} = \frac{2}{\left(\frac{z_s}{z_0} + 1\right)\left(\frac{z_0}{z_L} + 1\right)e^{\gamma t} + \left(\frac{z_s}{z_0} - 1\right)\left(\frac{z_0}{z_L} - 1\right)e^{-\gamma t}},$$
 (1)

where  $\gamma$  is the propagation constant and  $z_0$  is the characteristic

$$z_0 = \sqrt{\frac{L_t}{C_t}} \sqrt{1 + \frac{R_t}{SL_t}}, \quad \text{and} \quad \gamma l = S \sqrt{L_t C_t} \sqrt{1 + \frac{R_t}{SL_t}}.$$
 (2)

For a CMOS gate driving another CMOS gate at the end of the line,  $z_s = R_{tr}$  and  $z_L = 1/SC_L$ . A time scaling is applied by substituting t'/  $\omega_n$  for each t where

$$\omega_n = \frac{1}{\sqrt{L_t(C_t + C_L)}}. (3)$$

From the characteristics of the Laplace transform, the complex frequency S is substituted by  $\omega_n S$ . With this time scaling, the variables  $\gamma$ ,  $z_0$ , and  $z_L$  are transformed to  $\gamma'$ ,  $z'_0$ , and  $z'_L$ , respectively, which can be evaluated by substituting  $\omega_n S'$  for each S. If the exponential functions in the transfer function in (2) are replaced by a series expansion, the transfer function becomes

$$\frac{V_{out}(S')}{V_{in}(S')} = \frac{1}{\left(1 + \frac{z_s}{z'_L}\right)\left(1 + \frac{(\gamma'l)^2}{2!} + \dots + \left(\frac{z_s}{z'_0} + \frac{z'_0}{z'_L}\right)\left((\gamma'l) + \frac{(\gamma'l)^3}{3!} + \dots \right)}.$$
 (4)

Substituting for  $\gamma' l$ ,  $z'_0$ , and  $z'_L$ , the transfer function  $V_{out}(S')/V_{in}(S')$ is a function of only three variables:  $\zeta$ ,  $R_T$ , and  $C_T$  which are

$$R_T = \frac{R_{rr}}{R_r}, \qquad C_T = \frac{C_L}{C_r}, \qquad \text{and} \qquad (5)$$

$$R_{T} = \frac{R_{tr}}{R_{t}}, \qquad C_{T} = \frac{C_{L}}{C_{t}}, \qquad \text{and} \qquad (5)$$

$$\zeta = \frac{R_{t}}{2} \sqrt{\frac{C_{t}}{L_{t}}} \cdot \frac{R_{T} + C_{T} + R_{T}C_{T} + 0.5}{\sqrt{(1 + C_{T})}}. \qquad (6)$$

The first few terms of the series expansion in S' are

$$\frac{V_{out}(S)}{V_{in}(S)} = \frac{1}{1 + 2\zeta S' + \left(\frac{0.5 + C_T}{1 + C_T} + 16\zeta^2 \left(1 - \frac{R_T^2 + C_T^2 + (R_T C_T)^2}{(R_T + C_T + R_T C_T + 0.5)^2}\right)\right) S'^2 + \cdots}$$
(7)

Thus, for a unit step input function, the output voltage waveform  $V_{out}(t') = (1/S)^* V_{out}(S')/V_{in}(S')$  is also a function of the three variables  $\zeta$ ,  $R_T$ , and  $C_T$ . The scaled 50% propagation delay  $t'_{pd}$  can be calculated by solving  $V_{out}(t'_{pd}, \zeta, R_T, C_T) = 0.5$  which means that  $t'_{pd}$  is only a function of  $\zeta$ ,  $R_T$ , and  $C_T$ . Thus, the propagation delay of an RLC line with a source resistance  $R_{tr}$  and a load capacitance  $C_L$  has the form,

$$t_{pd} = \frac{t_{pd}(\zeta, R_T, C_T)}{\omega_n}.$$
 (8)

Note that this solution is characteristic of an *RLC* line and that no approximations have been made in deriving this result.

The scaled propagation delay  $t'_{pd}$  is dimensionless since  $\omega_n$  has the units of 1/time.  $t'_{pd}$  is a function of only three variables which is the canonical number of variables to describe  $t'_{pd}$ . There are several ways to select these three variables. The three variables chosen here are  $R_T$ ,  $C_T$ , and  $\zeta$  since these variables are physically intuitive. The variables  $R_T$  and  $C_T$  characterize the relative significance of the gate parasitic impedances with respect to the interconnect parasitic impedances. Increasing  $R_T$  and  $C_T$  demonstrates that the gate parasitic impedances further affect the propagation delay. The third variable  $\zeta$  is the coefficient of  $S^I$  in the denominator of the transfer function.  $\zeta$  is chosen as the third variable since the 50% delay is primarily dependent upon the coefficients of  $S^{l}$  in the denominator and the numerator [13]. This characteristic is used to reduce the number of variables that affect the propagation delay from three to one  $(\zeta)$ . Note that the three variables  $R_T$ ,  $C_T$ , and  $\zeta$  are not independent since  $\zeta$  is a function of  $R_T$  and  $C_T$ .

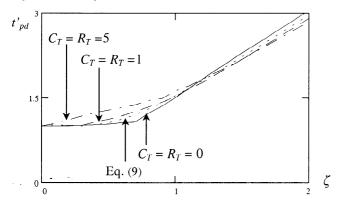


Fig. 2. Comparison of the accuracy of (9) to AS/X [14] simulations of the time scaled 50% propagation delay  $t'_{pd}$  of an RLC transmission line with a source resistance  $R_{tr}$  and a load capacitance  $C_L$ . The propagation delay is plotted versus  $\zeta$  for different values of  $R_T$  and  $C_T$ .

AS/X [14] simulations of the time scaled 50% propagation delay of a gate driving an RLC transmission line  $t'_{pd}$  as a function of  $\zeta$ ,  $R_T$ , and  $C_T$  are shown in Fig. 2. Note in Fig. 2 that the propagation delay is primarily a function of  $\zeta$ . The dependence on  $R_T$  and  $C_T$  is fairly weak. This characteristic does not imply that the transistor driving the interconnect and the load capacitance has a minor effect on the propagation delay since  $\zeta$  includes the effects of  $R_T$  and  $C_T$ . Note also that this effect is particularly weak in the range where  $R_T$  and  $C_T$  are between zero and one. This range is most important for global interconnect and long wires in current deep submicrometer technologies. Thus, the propagation delay is primarily a function of  $\zeta$ , which collects the five impedances that affect the propagation

delay,  $R_t$ ,  $L_t$ ,  $C_t$ ,  $R_{tr}$ , and  $C_L$ , into a single parameter. A curve fitting method is used to minimize the error when  $R_T$  and  $C_T$  are between zero and one, as illustrated in Fig. 2.

Using this approach, the propagation delay in the linear region can be modeled by the following function,

$$t_{pd} = (e^{-2.9\zeta^{1.35}} + 1.48\zeta)/\omega_n. \tag{9}$$

AS/X [14] simulations of the propagation delay of an RLC transmission line as compared to  $t_{pd}$  in (9) are shown in Table 1. Note that the solution exhibits high accuracy (the error is less than 5%) for a wide range of interconnect ( $R_t$ ,  $L_t$ , and  $C_t$ ) and gate impedances ( $R_t$  and  $C_L$ ). Note also that the simulation data listed in Table 1 include those cases where the response is underdamped and overshoots occur (high inductive effects), and those cases where the response is overdamped (low inductive effects). All of the above operating modes are described by one continuous equation, (9).

Table 1. Comparison of  $t_{pd}$  in (9) to AS/X simulations characterizing the propagation delay of a CMOS gate driving an *RLC* transmission line.  $C_t = 1$  pF and  $R_{tr} = 500 \Omega$ .

$R_{I}$	,	$C_{I} = 0.1$			$C_T = 0.5$			$C_T = 1.0$		
	$L_t$ H	(9)	ASX	Error	(9)	ASX	Error	(9)	ASX	Error
0.1	10-5	3389	3287	3.3%	3893	3782	2.9%	4469	4344	2.8%
	10 <sup>-6</sup>	1062	1071	0.8%	1277	1328	3.8%	1553	1627	4.5%
	10-7	532	552	3.6%	848	881	3.7%	1248	1269	1.6%
	10-8	508	496	2.4%	850	883	3.7%	1239	1261	1.7%
0.5	10 <sup>-5</sup>	3397	3304	2.8%	4086	3940	3.8%	4504	4518	0.3%
	10 <sup>-6</sup>	1145	1108	3.3%	1489	1509	1.3%	1946	2030	4.1%
	10-7	854	861	0.8%	1297	1300	0.2%	1812	1830	1.0%
	10-8	841	850	1.0%	1277	1283	0.5%	1811	1825	0.8%
1.0	10-5	3397	3291	3.0%	3897	3773	3.3%	4496	4383	2.6%
	10 <sup>-6</sup>	1070	1076	0.6%	1323	1345	1.6%	1712	1702	0.6%
	10-7	634	609	4.1%	930	910	2.2%	1297	1281	1.2%
	10-8	630	622	1.2%	936	913	2.5%	1294	1271	1.8%

An interesting special case is when the gate parasitic impedances ( $C_L$  and  $R_{tr}$ ) are neglected. This case is particularly important since it describes the propagation delay characteristics of a distributed RLC line without the distortion of the gate impedances. For the limiting case where  $L \to 0$ , (9) reduces to  $0.37RCl^2$ . This expression is the same formula for the propagation delay of a distributed RC line as described in [3] and [11]. Also note the well known square dependence on the length of the wire. For the other limiting case where  $R \to 0$ , the propagation delay is given by  $l\sqrt{LC}$ . Note the linear dependence on the length of the line. Thus, the traditional quadratic dependence of the propagation delay on the length of an RC line approaches a linear dependence as inductance effects increase.

#### III. Repeater Insertion into *RLC* Interconnect

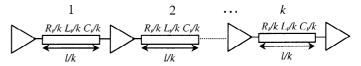


Fig. 3. Repeaters inserted in an *RLC* line to minimize the propagation delay.

Traditionally, repeaters are inserted into RC lines to partition an interconnect line into shorter sections, e.g., [9]-[11], thereby reducing the total propagation delay. Applying the same idea to the

general case of an *RLC* line, repeaters are used to divide the interconnect line into k sections as shown in Fig. 3. The buffers are each uniformly the same size and h times larger than a minimum size buffer. The buffer output impedance  $R_{tr}$  is  $R_0/h$  and the input capacitance of the buffer  $C_L$  is  $hC_0$ .

The total propagation delay of the repeater system is the sum of the individual propagation delays of the k sections and is a function of h and k for a given interconnect line. The values of h and k at which the total delay  $t_{pdtotal}$  is a minimum is determined by simultaneously solving the following two differential equations,

$$\frac{\partial t_{pdtotal}(h,k)}{\partial h} = 0 \quad \text{and} \quad \frac{\partial t_{pdtotal}(h,k)}{\partial k} = 0.$$
 (10)

For the special case of an RC line  $(L_t \rightarrow 0)$ , the solution for these equations is

$$h_{opt}(RC) = \sqrt{\frac{R_0 C_t}{R_t C_0}}$$
 and  $k_{opt}(RC) = \sqrt{\frac{R_t C_t}{2R_0 C_0}}$  (11)

These equations are the same as described by Bakoglu in [11].

Solving (10) for the general case of an RLC line is analytically intractable. However, as described in the appendix,  $h_{opt}$  and  $k_{opt}$  for an RLC line have the form,

$$h_{opt} = \sqrt{\frac{R_0 C_t}{R_t C_0}} \bullet h'(T_{L/R})$$
 and  $k_{opt} = \sqrt{\frac{R_t C_t}{2R_0 C_0}} \bullet k'(T_{L/R}),$  (12)

where  $h'(T_{L/R})$  and  $k'(T_{L/R})$  are error factors that account for the effect of the inductance and  $T_{L/R}$  is

$$T_{L/R} = \sqrt{\frac{L_{t}/R_{t}}{R_{0}C_{0}}} {.} {13}$$

The closed form solution for the propagation delay in (9) is used to characterize the delay of the repeater system shown in Fig. 3 as described in the appendix. The resulting expression is partially differentiated with respect to h and k and the two derivatives are equated to zero. The resulting two equations are solved numerically for the optimum values of h and k. Numerical solutions for  $h_{opt}$  and  $k_{opt}$  in (10) for different values of  $T_{LR}$  are plotted in Fig. 4.

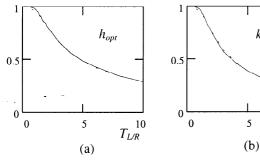


Fig. 4. Numerical solutions of (10) compared to eqs. (14) and (15). a)  $h_{opt}$  as compared to (14). b)  $k_{opt}$ , as compared to (15). Numerical solutions are shown by the solid line while (14) and (15) are shown by the dashed line.

Curve fitting is employed to determine a function that accurately characterizes  $h_{opt}$  and  $k_{opt}$ . These functions are

$$h_{opt} = \sqrt{\frac{R_0 C_t}{R_t C_0}} \frac{1}{\left[1 + 0.16 (T_{total})^3\right]^{0.24}},$$
(14)

and

$$k_{opt} = \sqrt{\frac{R_i C_i}{2R_0 C_0}} \frac{1}{\left[1 + 0.18 (T_{IJR})^3\right]^{0.3}}.$$
 (15)

These closed form solutions are highly accurate with an error in the total propagation delay of the repeater system of less than 0.05% as compared to numerical analysis. These formulae can therefore be considered exact for all practical purposes.

Upon examination of (14) and (15),  $h_{opt}$  and  $k_{opt}$  are equal to  $h_{opt}(RC)$  and  $k_{opt}(RC)$  in (11) for the special case of an RC impedance when  $L_t \to 0$  (or  $T_{LR} \to 0$ ). Note that the error between the two cases increases as  $T_{L/R}$  increases. This behavior is understandable since inductance effects are more significant as  $T_{L\!R}$  increases (which increases the error of neglecting  $L_t$ ). Also note that as  $T_{LR}$  increases (or the inductance effects increase), the number of sections  $k_{opt}$ decreases. The improvement achieved by partitioning the line into shorter sections in the RC case is primarily due to the quadratic dependence of the propagation delay on interconnect length. In the other extreme case of an LC line, the propagation delay is linear with interconnect length and therefore no speed improvement is achieved by partitioning the line into shorter subsections. Actually, adding repeaters in this case would only increase the total propagation delay because of the additional gate delay of the repeaters. Thus, as inductance effects increase, the optimum number of repeaters to insert to minimize the total interconnect delay decreases.

The per cent increase in  $t_{pdiotal}$  caused by neglecting inductance and treating an RLC line as an RC line as compared to including inductance based on (14) and (15) for  $h_{opt}$  and  $k_{opt}$ , respectively, is

$$\% \text{Increase} = \frac{100 * \left[ (t_{pdiotal})_{RC} - (t_{pdiotal})_{RLC} \right]}{(t_{pdiotal})_{RLC}}.$$
 (16)

 $(t_{pdtotal})_{RC}$  is calculated by substituting the solution for  $h_{opt}(RC)$  and  $k_{opt}(RC)$  in (11) into  $t_{pdtotal}$ .  $(t_{pdtotal})_{RLC}$  is calculated by substituting the solution for  $h_{opt}$  and  $k_{opt}$  in (14) and (15), respectively, into  $t_{pdtotal}$ . The resulting solution is a function of  $T_{L/R}$  only and can be accurately approximated by

$$\% Increase = \frac{30}{\sqrt{\left(1 + \frac{0.5}{T_{L/R}} + 23e^{-0.8T_{L/R}} + 10^4 e^{-4T_{L/R}}\right)}}$$
(17)

Note that  $(t_{pdtotal})_{RC}$  is larger than  $(t_{pdtotal})_{RLC}$  as  $T_{LR}$  increases. For  $T_{LR} = 3$ ,  $t_{pdtotal}$  increases by 10%, for  $T_{LR} = 5$ ,  $t_{pdtotal}$  increases by 20%, and for  $T_{LR} = 10$ ,  $t_{pdtotal}$  increases by 30%.

The total area of the buffers in the repeater system is given by  $A_{RLC} = h_{opt} * k_{opt} * A_{min}$  and  $A_{RC} = h_{opt} (RC) * k_{opt} (RC) * A_{min}$  for the RLC and the RC case, respectively.  $A_{min}$  is the area of a minimum size buffer. The per cent area increase %AI is characterized by  $100*(A_{RC} - A_{RLC})/A_{RLC}$  and is

$$\%AI = 100* \left\{ \left[ 1 + 0.18 \left( T_{L/R} \right)^3 \right]^{0.3} * \left[ 1 + 0.16 \left( T_{L/R} \right)^3 \right]^{0.24} - 1 \right\}.$$
 (18)

The per cent area increase for  $T_{LR}=3$  is 154% and for  $T_{LR}=5$  is 435%. Using the impedance values described in [7], it can be shown that  $T_{LR}=5$  is common for a current 0.25 µm technology. Thus, neglecting inductance not only increases the total delay of the repeater system but significantly increases the buffer area as well. This trend is expected since treating the interconnect as an RC line and neglecting inductance requires more repeaters. These additional repeaters add to the total delay and buffer area without reducing the line delay because significant inductance makes the dependence of the delay on the length of the interconnect become sub-quadratic. Note that  $T_{LR}$  increases as  $R_0C_0$  decreases. This relation means that as the gate delay decreases, inductance becomes more important. Thus, the effects of inductance in next generation design methodologies will become fundamentally important as technologies scale.

10

 $T_{L/R}$ 

#### **IV. Conclusions**

Closed form solutions for the propagation delay of a CMOS gate driving a distributed RLC load are presented that are within 5% of AS/X simulations. It is shown that the traditional quadratic dependence of the propagation delay on the length of an RC line tends to a linear dependence as inductance effects increase. This behavior is expected to have a profound effect on future high speed CMOS technologies.

Closed form solutions are presented for inserting repeaters into RLC lines that are highly accurate with respect to numerical solutions. Inserting repeaters based on an RC model into RLC lines as compared to applying a distributed RLC impedance model of the interconnect increases the propagation delay by up to 30%, and the repeater area by up to 435% for common VLSI interconnect. The power consumption of the repeater system is also expected to be much less in the case of an RLC model as compared to an RC model due to the increased repeater area for the RC case. Thus, incorporating inductance into the interconnect impedance model is of crucial importance for accurately estimating the propagation delay of on-chip interconnect as well as for minimizing the propagation delay. This importance is expected to increase as the gate parasitic impedances decrease and as technologies increase in speed.

## Appendix

## **Optimum Repeater Insertion in RLC Lines**

As shown in section II, the propagation delay of a gate driving a single section of interconnect with an impedance of  $R_b$ ,  $C_b$  and  $L_t$  has the form given by (8). If repeaters are inserted to partition the line into k sections and each repeater is h times greater than a minimum size inverter, the total propagation delay of the system is the summation of the propagation delays of each of the individual sections. Since the sections are each equal, the total delay can be expressed as  $t_{pdiotal} = kt_{pdsec}$ , where  $t_{pdsec}$  is the propagation delay of a single section. Each section has an interconnect impedance equal to  $R_t/k$ ,  $C_t/k$ , and  $L_t/k$ . Since each repeater is h times larger than a minimum size buffer, each repeater has an output resistance  $R_{tr} = R_0$ h and a load capacitance of  $C_L = C_0 h$ . Thus, the total propagation delay of the repeater system

$$t_{pdiotol} = k \cdot \frac{t_{pd}(\zeta_{\text{sec}}, R_{T \text{sec}}, C_{T \text{sec}})}{\omega}, \tag{19}$$

$$t_{pdiotal} = k \cdot \frac{t_{pd}(\zeta_{sec}, R_{T sec}, C_{T sec})}{\omega_{n sec}},$$
where  $R_{T sec}$  and  $C_{T sec}$  are
$$R_{T sec} = \frac{k}{h} \frac{R_0}{R_t} \quad \text{and} \quad C_{T sec} = kh \frac{C_0}{C_t}.$$
(20)

$$\zeta_{\text{sec}} = \frac{R_t}{2k} \sqrt{\frac{C_t}{L_t}} \cdot \frac{R_{T \text{sec}} + C_{T \text{sec}} + R_{T \text{sec}} C_{T \text{sec}} + 0.5}{\sqrt{(1 + C_{T \text{sec}})}},$$
(21)

$$\omega_{n \, \text{sec}} = \frac{k}{\sqrt{L_t C_t} \sqrt{1 + C_T \, \text{sec}}}.$$
 (22)

Guided by the solution of h and k for the special case of an RC line, the solution for an RLC line is in the form of

$$h = \sqrt{\frac{R_0 C_i}{R_i C_0}} \bullet h' \quad \text{and} \quad k = \sqrt{\frac{R_i C_i}{2R_0 C_0}} \bullet k', \tag{23}$$

where h' and k' are error factors that incorporate the existence of inductance and approach one as the inductance approaches zero. Substituting these values for h and k into (20), (21), and (22), the

variables 
$$R_{Tsec}$$
,  $C_{Tsec}$ ,  $\zeta_{sec}$ , and  $\omega_{nsec}$  become
$$R_{Tsec} = \frac{k'}{h'\sqrt{2}}, \qquad C_{Tsec} = \frac{h'k'}{\sqrt{2}}, \qquad (24)$$

$$\zeta_{\text{sec}} = \frac{1}{\sqrt{2}k'T_{LIR}} \cdot \frac{R_{T\,\text{sec}} + C_{T\,\text{sec}} + R_{T\,\text{sec}}C_{T\,\text{sec}} + 0.5}{\sqrt{(1 + C_{T\,\text{sec}})}},$$
(25)

and

$$\frac{k}{\omega_{n \, \text{sec}}} = \sqrt{L_t C_t} \sqrt{(1 + C_{T \, \text{sec}})},\tag{26}$$

where  $T_{LR}$  is given by

$$T_{L/R} = \sqrt{\frac{L_t/R_t}{R_0 C_0}} {27}$$

Thus, the total propagation delay has the form,

$$t_{pdiotal} = \sqrt{L_t C_t} \cdot f(h', k', T_{L/R}) \cdot \tag{28}$$

Determining the values of k' and h' that minimize the total propagation delay requires the simultaneous solution of the following two differential equations,

$$\frac{\partial f(h', k', T_{L/R})}{\partial h'} = 0 \quad \text{and} \quad \frac{\partial f(h', k', T_{L/R})}{\partial k'} = 0. \quad (29)$$

The solution of these equations demonstrates that h' and k' are only functions of  $T_{L/R}$ . Thus, the optimum number of sections  $k_{opt}$  and the

optimum repeater size 
$$h_{opt}$$
 for an  $RLC$  interconnect is
$$h_{opt} = \sqrt{\frac{R_0 C_t}{R_t C_0}} \bullet h'(T_{L/R}) \quad \text{and} \quad k_{opt} = \sqrt{\frac{R_t C_t}{2R_0 C_0}} \bullet k'(T_{L/R}). \tag{30}$$

Note that this solution is characteristic of an RLC line and that no approximations have been made in deriving this result.

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